

Serial No. 09/880,465

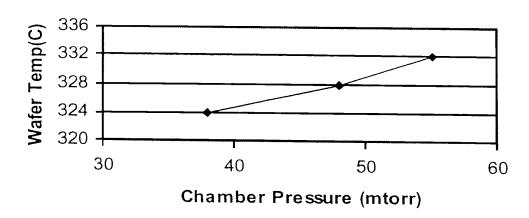


FIG. 1



Atomic Concentration (%)

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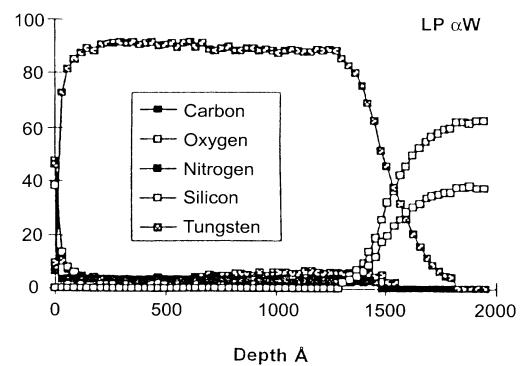
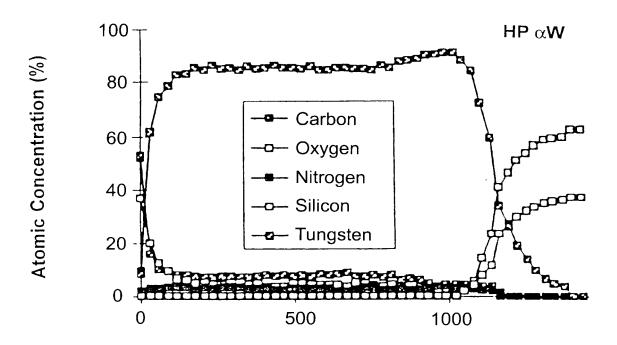


FIG. 2A



Depth Å



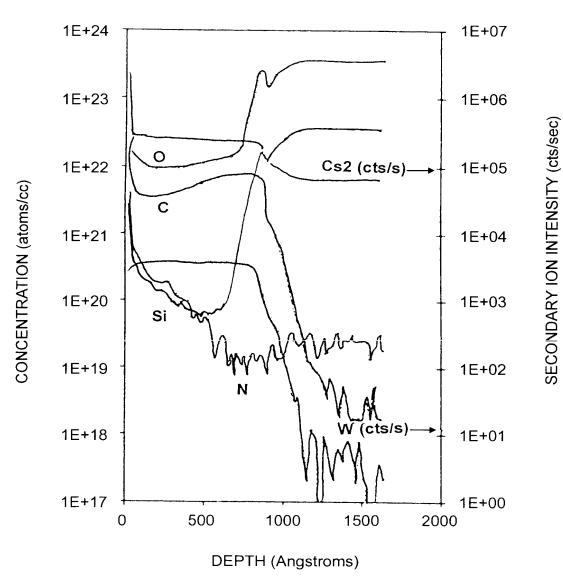
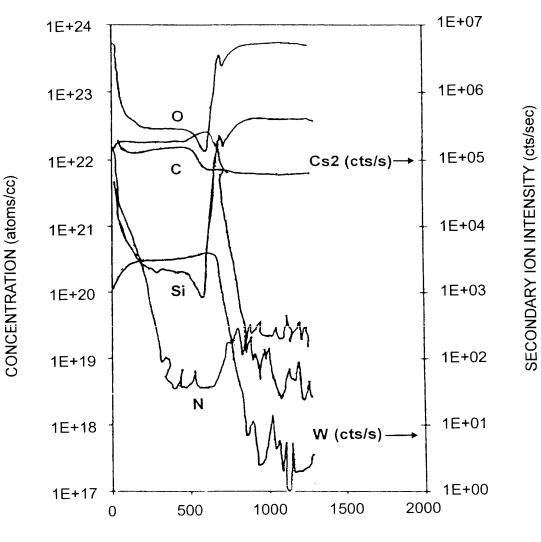


FIG. 3A



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**DEPTH** (Angstroms)

FIG. 3B



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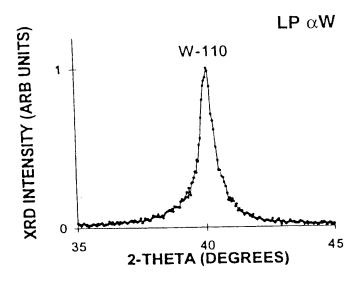


FIG. 4A

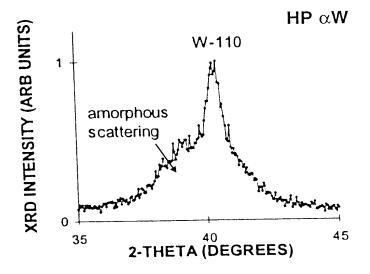


FIG. 4B



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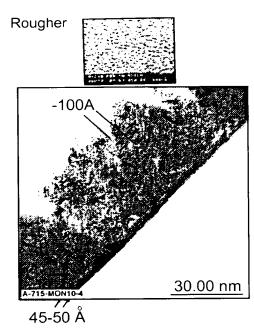


FIG. 5A

 $\text{HP }\alpha \text{W}$ 

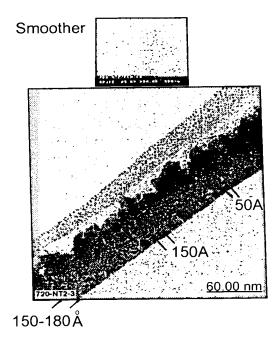


FIG. 5B